

Focus on nanotechnology

The International Textile Machinery Exhibition (ITMA) 2007, scheduled for Sept. 13–20 in the New Munich Trade Fair Centre, will have a special focus on the uses of nanotechnology in fibers, textiles and treatments, as part of the show's "A Place for Innovation" theme.

Many multifunctional nanotex developments have already been launched in the textile industry markets: extremely high-insulation thermal protective clothing, or self-cleaning textile surfaces from which even substances like catsup or red

will drip off; and textile structures with miniaturized electronics producing smart clothing that perceives and reacts to environmental (or bodily) conditions. In another example, a Japanese fiber manufacturer has developed a patented process by which the properties of top-quality merino wool can be achieved on polyester fibers.

There are already scientists warning consumers and industry about the possible environmental and health dangers that might result from unrestrained production with nanotechnology. To address these concerns at least partially, textile research institutes have developed quality labels on the basis of defined test procedures for consumer safety and assurance. The Institute of Textile Technology and Process Engineering Denkendorf (ITV)

has created the Denkendorf Label of Quality for Self-Cleaning Textiles, and the Hohenstein Institute offers the Hohenstein Quality Label Nanotechnology.

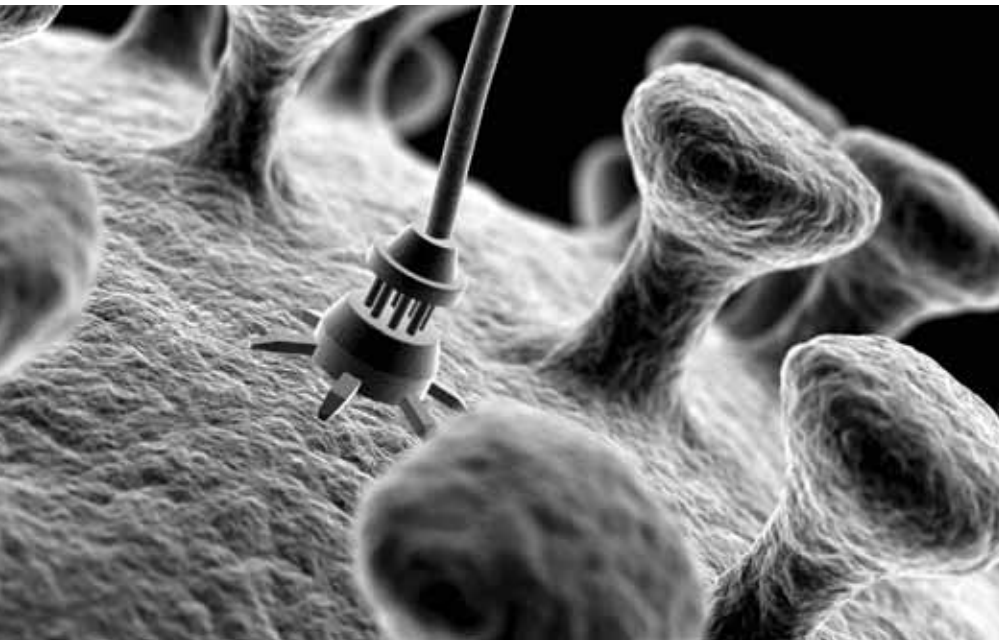
Manufacturers of textile machines (especially for finishing machines), textile auxiliary manufacturers and component suppliers will increasingly promote the advantages of these new technologies at ITMA 2007. The show will also display a complete range of textile developments, from fiber to clothing, with nanotechnology a topic in all areas. For details about the trade show, visit www.itma.com.

Triennial showcase for the sewn products industry

Building upon the success of the 2004 edition, the Sewn Products Equipment & Suppliers of the Americas (SPESA), owner and producer of SPESA Expo 2007, and Urban Expositions, owner and producer of Material World, will once again co-locate their events in 2007, from May 8–10 at the Miami Beach Convention Center. (Material World is an official event of the American Apparel & Footwear Association.) This year's event will also feature Technology Solutions, an IT-focused event jointly owned and produced by SPESA and Urban Expositions, which will showcase all aspects of information technology solutions for the sewn products industry.

An open floor plan, single admission badge and unified educational program will provide visitors the opportunity to experience these three shows in one place, at one time. Visitors to the 2007 event will be able to see machinery, parts, fabric, trims, services, CAD/CAM, software, sourcing, and accessories along the entire supply chain.

For more details about the triennial event, visit www.spesaexpo.com, www.materialworld.com, or www.techsolutionsexpo.com.



Connections is a forum for news and information from cooperating organizations within or connected to the specialty fabrics industry. For news from the Industrial Fabrics Association International, publisher of the *Review*, turn to IFAI Update on page 68.

Online technical journal debuts

Three well-known trade associations and a prestigious professional society have entered into a partnership to publish the *Journal of Engineered Fibers and Fabrics (JEFF)*, an electronic publication of original research and advances in fibers, fibrous materials and their components.

The American Association of Textile Chemists & Colorists (AATCC) joined founding partners INDA, Association of the Nonwoven Fabrics Industry; TAPPI (Technical Association of the Pulp and Paper Industry) and The Fiber Society as a sponsor of the journal.



An international, peer-reviewed E-journal that publishes original research on all aspects of fabric technologies and their value chain from raw materials to end-use products, *JEFF* replaced the *International Nonwovens Journal* earlier this year; two issues were produced in late 2006, with four more planned for 2007.

The new journal utilizes publishing software that makes it easier for authors all over the world to submit a paper electronically, and for the editors and peer reviewers to provide electronic feedback. To review manuscript requirements and/or to submit a paper, visit <http://jeff.edmgr.com>. Papers are posted on the journal Web site as soon as they are approved. Bill Haile, managing editor of *JEFF*, can be reached at jeffjournal@charter.net. 